Am ndm nts to th Claims

The listing of claims will replace all prior v rsions, and listings, of claims in the application:

Listing of Claims

Claims 1-3 (cancelled)

- 4. (previously presented) The cleaning wipe of Claim 23 wherein the acetylenic diol is present in the range of 0.01% to 0.3% by weight.
- 5. (previously presented) The cleaning wipe of Claim 4 wherein the acetylenic diol is present in the range of 0.05% to 0.2% by weight.
- 6. (previously presented) The cleaning wipe of Claim 5 wherein the acetylenic diol has a vapor pressure of at least 1 \times 10⁻⁴ torr at 25°C.
- 7. (previously presented) The cleaning wipe of Claim 6 wherein the acetylenic diol has a vapor pressure of at least 1×10^{-3} torr at 25° C.
- 8. (previously presented) The cleaning wipe of Claim 7 wherein the acetylenic diol is dimethyl octynediol.
- 9. (previously presented) The cleaning wipe of Claim 7 wherein the acetylenic diol is tetramethyl decynediol.
- 10. (previously presented) The cleaning wipe of Claim 4 wherein the wipe substrate is selected from the group consisting of: cotton, abaca, polyester, nylon,

polyester/cellulose, rayon, polypropylene, rayon/polyester, polypropylene/cellulose, polyurethane, cotton/polyester and mixtures thereof.

11. (previously presented) The cleaning wipe of Claim 4 wherein the acetylenic diol is selected from the group consisting of: dimethyl octynediol; tetramethyl decynediol; 2,6,9,13-tetramethyl-2,12-tetradecadien-7-yne-6-9-diol; 2,6,9-trimethyl-2-decen-7-yne-6-9-diol; 7,10-dimethyl-8-hexadecyne-7,10-diol; 2,4,7,9-tetramethyl-5-decyne-4,7-diol; 4,7-dimethyl-5-decyne-4,7-diol; 3,6-diethyl-4-octyne-3,6-diol; 2,5-dicycloprpyl-3-hexyne-2,5-diol; 2,5-diphenyl-3-hexyne-2,5-diol; 3,5-dimethyl-1-hexyn-3-ol, 2,5,8,11-tetramethyl-6-dodecyne-5,8-diol and mixtures thereof.

12. (cancelled)

- 13. (previously presented) The cleaning wipe of Claim 11 wherein the wipe substrate is a fibrous substrate.
- 14. (previously presented) The cleaning wipe of Claim 11 wherein the wipe substrate is a woven fibrous substrate.
- 15. (previously presented) The cleaning wipe of Claim 11 wherein the wipe substrate is a nonwoven fibrous substrate.
- 16. (previously presented) The cleaning wipe of Claim 11 wherein the wipe substrate is a sponge.

- 17. (previously presented) The cleaning wipe of Claim 11 wherein the water is high purity water.
- 18. (previously presented) The cleaning wipe of Claim 11 wherein the water is deionized water.
- 19. (previously presented) The cleaning wipe of Claim 11 wherein the water is distilled water.
- 20. (previously presented) A prewetted cleaning wipe for cleaning surfaces in an electronic materials fabricating area having a low volatile organic chemical content in the range of 0.001% to 0.5% by weight and low nonvolatile residue property of at least 1 x 10⁻⁴ torr at 25°C comprising; a woven fibrous polyester/cellulose wipe substrate wetted with an aqueous solution consisting essentially of high purity water selected from the group consisting of distilled water and deionized water, and from 0.001 % to 0.5% by weight of an acetylenic diol surface active agent selected from the group consisting of dimethyl octynediol, tetramethyl decynediol and mixtures thereof.

21. (cancelled)

- 22. (previously presented) The cleaning wipe of Claim 20 wherein the acetylenic diol surface active agent is present in an amount from 0.05% to 0.2% by weight.
- 23. (previously presented) In a cleaning wipe for use in cleaning an electronics fabrication industry clean room comprising a wipe substrate wetted with a cleaning solution,

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the improvement which resides in a cleaning wipe having low volatile organic chemical and low nonvolatile residue properties comprising a wipe substrate wetted with a solution consisting essentially of water and from 0.001% to 0.5% by weight of an acetylenic diol.